	Hits	Search Text	DBs
19	9	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light$3 near5 sensitive) or photoresist or resist or sensitive)) and (modulat$4 or (spatial near14 modulat$4) or SLM or deflect$4 or acousto$6) and (immers$4 near9 (liquid or fluid)) and ((capillary near9 force) or capillarit$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
20	27	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light$3 near5 sensitive) or photoresist or resist or sensitive)) and (modulat$4 or (spatial near14 modulat$4) or SLM or deflect$4 or acousto$6) and ((immers$4 near12 (liquid or fluid)) same (inlet or outlet or port or input or output))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB